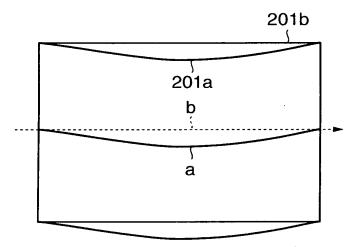
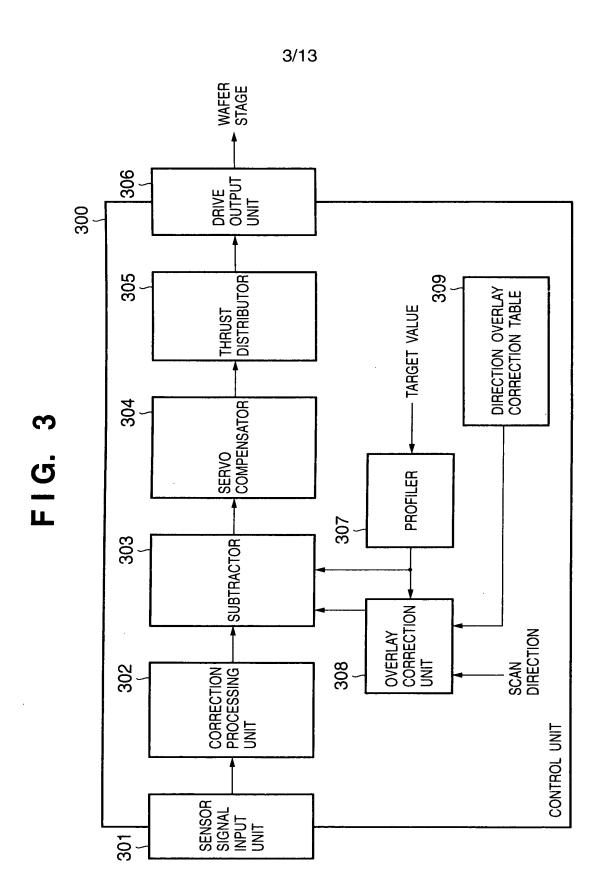
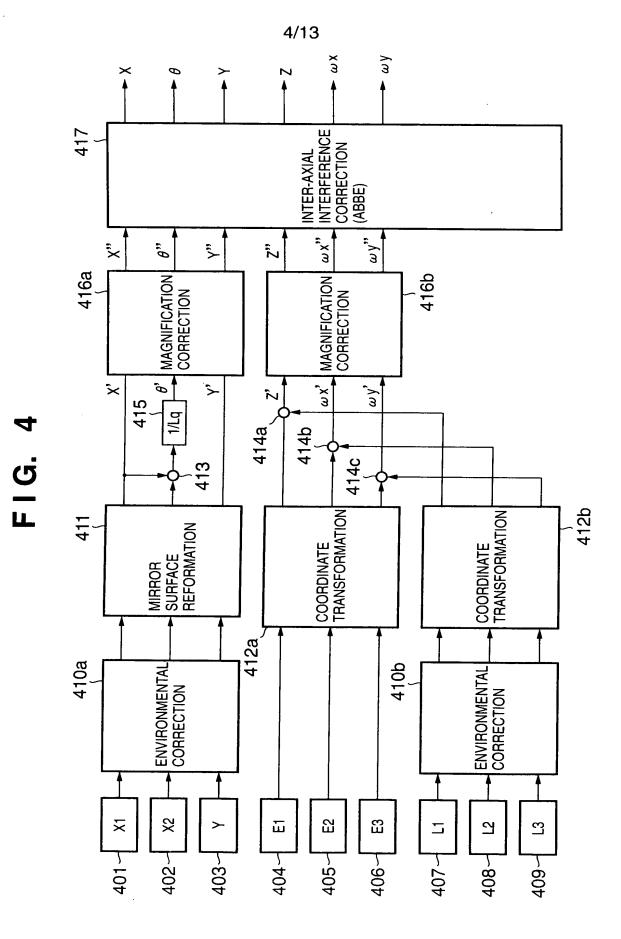
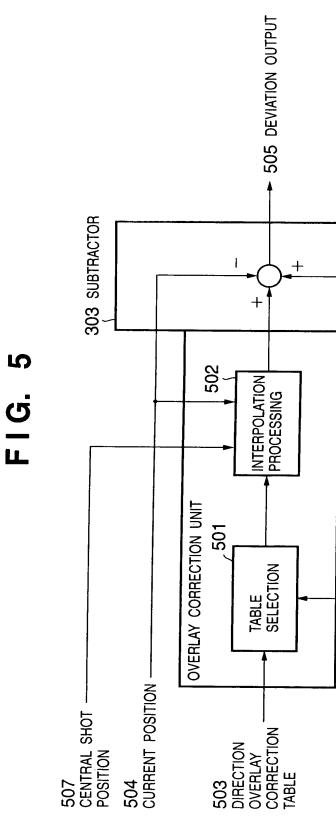


FIG. 2









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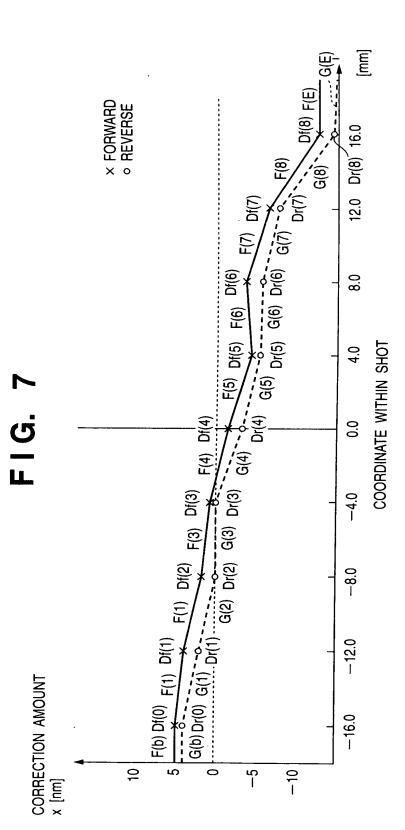
508 PROFILE

308

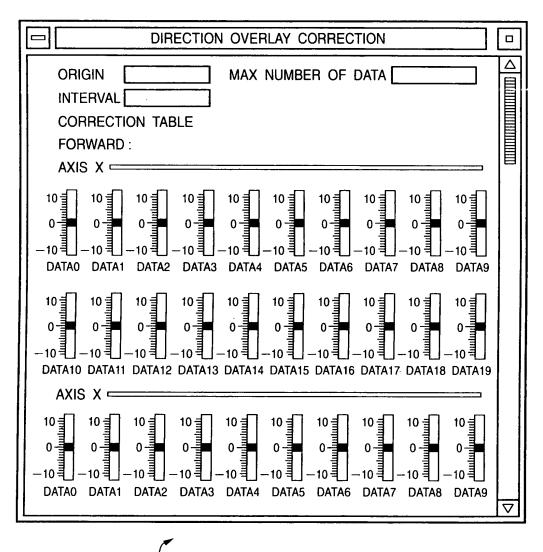
506 SCAN DIRECTION

# FIG. 6

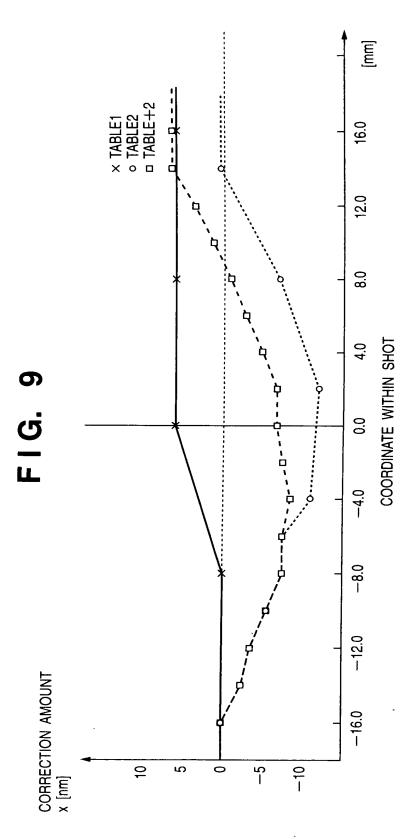
ORIGIN INTERVAL CORRECTION (FORWARD)	-16.000 4.000 N DATA		[mm] [mm] [nm/ppb]		
X 5 4 2 1 -1 -4 -3 -6	Y 1 1 0 -1 -4 -2 -4 -5	Z 10 8 10 12 13 10 7 4	Qx 0 10 20 20 20 40 10	Qy - 10 - 10 20 40 30 40 50 80	Qz 20 10 10 10 0 -10 -30 -30
-12  (REVERSE)  X  4  2  0  0  -3  -5  -5  -7  -14	-9  Y 0 0 -1 -1 -4 -3 -4 -5 -9	0 Z 9 6 11 10 9 6 4 -1	-20 Qx 10 0 10 20 40 20 20 10 0	Qy -10 0 10 30 10 40 60 100 80	-40  Qz 20 10 10 20 0 -10 -30 -30 -30



### FIG. 8



1001



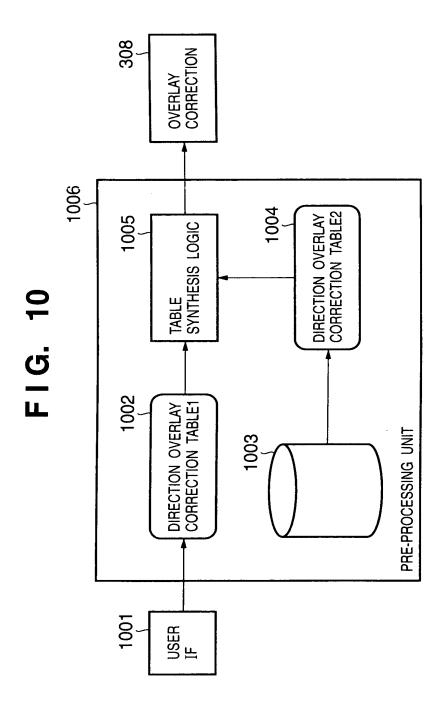
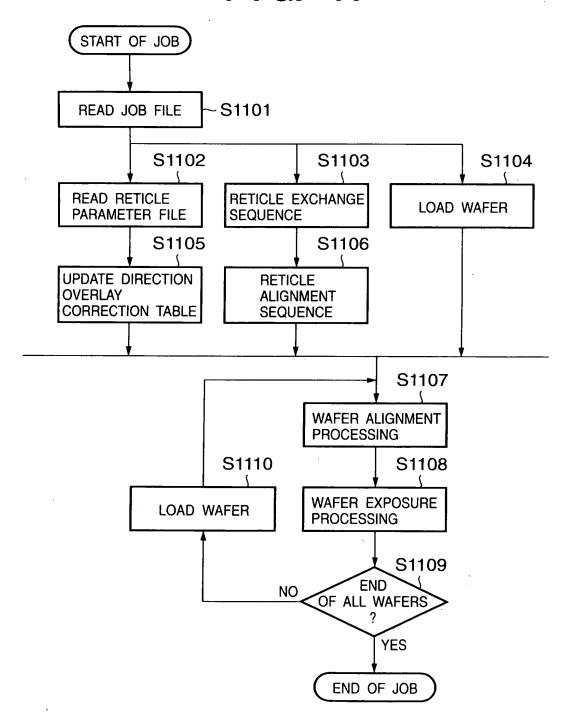
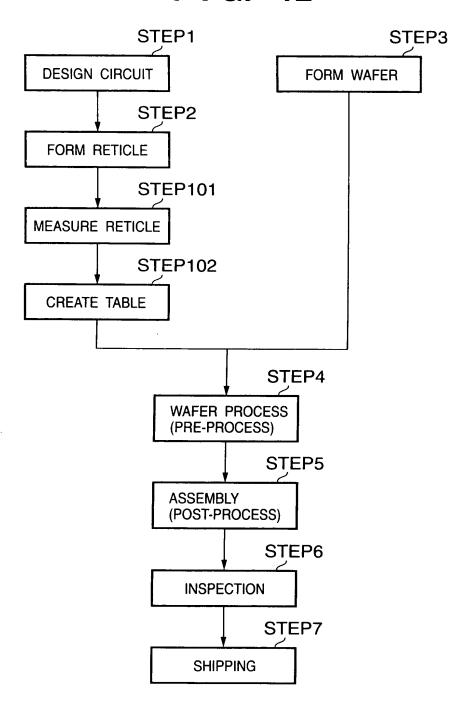


FIG. 11



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# FIG. 12



SEMICONDUCTOR DEVICE MANUFACTURING FLOW

## FIG. 13

